

Product Identification

Film Name: LPCVD Standard Nitride
 Process ID: D02LSN
 Scientific: Silicon Nitride - SiN
 Classification: Standard

Features

Low Cost
 Variable Processing Parameters
 Large Batch Capacity
 Custom Fixturing Available

Standards & Guarantees

Inspection: Standard I/O - First & Last
 Guaranteed: Thickness (On Si Monitors)
 Guaranteed: Refractive Index (On Si Monitors)

Items may vary when ordering outside the standard

Other Information

- Thicknesses of 3000A or greater: LPCVD Silicon Nitride is a stoichiometric film with a highly intrinsic tensile stress, which induces cracking and delamination at thicknesses beyond 3000A. LPCVD Silicon Nitride is available up to 4000A thickness but carries no warranty against delamination beginning at 3000A. Strataglass offers two silicon rich formulas for reducing the bulk film stress. If you need thicknesses beyond 3KA please also consider our product types: "LPCVD Zero Stress Nitride" and "LPCVD Low Stress Nitride".

Applications

Passivation
 Encapsulation
 Insulation Layer
 Inter-layer Dielectric
 Adhesion Layer
 Wear Coating
 Masking
 Barrier Layer
 Patterning

Film Specifications

Film Thickness	Standard	1,000A to 2,500A ± 10%
	Adjustable Range	250A to 4,000A
Refractive Index	Standard	2.00 ± .05
	Adjustable Range	Fixed
Film Uniformity	Edge to Edge	10%
	Across Load	10%
Deposition Temp	Standard	780C
	Adjustable Range	Fixed
Film Stress	Standard	800 to 1200 MPa
	Adjustable Range	Fixed

Film Properties

Electrical	Insulating Quality	Very Good
	Dielectric Constant	N/A
Mechanical	Hydrogen Inclusion	Low
	Scratch Protect	Very Good
	Masking Ability	Good
	Diffusion Barrier	Very Good
	Thermal Stability	Very Good
Etch Rate	BOE (50%)	Very Slow
	KOH	N/A
	Plasma	Moderate
Hydrology	Hydrophobic	Weak